

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Applicant(s):** Cyril Cabral, Jr., et al.      **Examiner:** Long Pham  
**Serial No:** 10/662,900      **Art Unit:** 2814  
**Filed:** September 15, 2003      **Docket:** YOR920030218US1(16714)  
**For:** REDUCTION OF SILICIDE FORMATION TEMPERATURE ON  
SiGe CONTAINING SUBSTRATES  
**Confirmation No:** 1278      **Dated:** December 21, 2006

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE UNDER 37 C.F.R. § 1.116**

Sir:

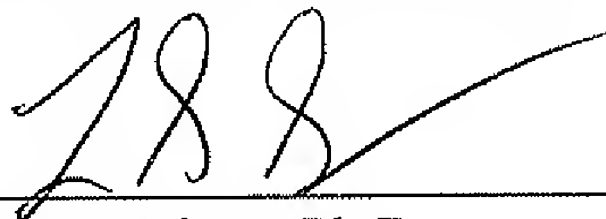
In response to the Office Action dated October 24, 2006, applicants submit the following amendments and remarks for entry into the record of the above-identified patent application.

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**CERTIFICATION OF ELECTRONIC TRANSMISSION**

I hereby certify that this document is being filed in the United States Patent and Trademark Office on the date shown below via electronic transmission.

Dated: December 21, 2006

  
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Leslie S. Szivos, Ph.D.